

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("4848141").PN.  IDS - bolmanger 1st,	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:06
2	L2	4	(("6340628") or ("6734533")).PN.  parent	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:06
3	L3	3	<del>("2007009717").PN.</del>  opp's P6 Pa	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:07
4	L4	0	L3 and <del>(Kanaya Okayama)</del>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08
5	L5	2	("2007009717").PN.  This case! P6 Pub	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08
6	L6	1	L5 and <del>(Kanaya Okayama)</del>  meaning search	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08

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10/802,991

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	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("20050194619").PN. from 8/14/07 JDS	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:20

not in ref. tool manager

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	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("20070009717").PN. <i>This case P6 Pub</i>	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:21
2	L2	1	L1 and (Kanaya Okayama damascene CMP polishing)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:23
3	L3	29	(("7164206") or ("6992391") or ("6566757") or ("6846737") or ("6703324") or ("6984581") or ("6432811") or ("6472315") or ("6593650") or ("7115995") or ("7192856") or ("6057226") or ("6417098")).PN.	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:25
4	L4	4	L3 and (EB "e-beam" ebeam (e electron) near (beam ray stream gun bombard\$7))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:28
5	L5	25	L3 not L4	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:45
6	L6	113284	(CDO SIOCH SiCOH (oxide dioxide SiO SiO2 "SiO.sub.2" "SiO.sub.2")) near3 ((C carbon organic) near (dop\$7 impurity residue) organic polymer\$7 hybrid)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:00

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	L #	Hits	Search Text	DBs	Time Stamp
7	L7	2213	(Dielectric low adj K) near3 ((C carbon organic carbonaceous) near (dop\$7 impurity residue sacrificial) hybrid pore adj form\$5)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:00
8	L8	113321	(CDO SIOCH SiCOH (oxide dioxide SiO SiO2 "SiO.sub.2" "SiO.sub.2")) near3 ((C carbon carbonaceous organic) near (dop\$7 impurity residue) organic polymer\$7 hybrid)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:01
9	L9	585	(L7 or L8) same(EB "e-beam" ebeam (e electron) near (beam ray stream gun bombard\$7))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:02
10	L10	2510	(427/496-507,551,552).CCLS.	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:03
11	L11	13 <sup>1</sup>	L9 and L10	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:03
12	L12	78	L9 and "438"/\$.CCLS.	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:04
13	L13	76	L12 not L11	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:05

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14	L14	40	L13 and damascene <i>includes parent's P6 Pub</i>	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:05
15	L15	36	L12 not (L11 or L14)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:06
16	L16	39	(L9 and (damascene CMP chemical adj mechanical adj polish\$5)) not (L11 or L14 or L15)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:08
17	L17	19	(L9 same (interlevel interlayer intern adj (level layer) wiring copper)) not (L11 or L14 or L15)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:09
18	L18	51	L16 or L17 <i>contains the cases P6 Pub</i>	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:10

*- Copied 10/16/2007 13:10's P6 Pub*

Day : Tuesday  
Date: 10/16/2007

Time: 11:42:13

## PALM INTRANET

# Inventor Information for 10/802991

Inventor Name	City	State/Country
WONG, LAWRENCE D.	BEAVERTON	OREGON

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*for Inventor  
Name Search*

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 Date: 10/16/2007

Time: 11:42:25

**PALM INTRANET****Inventor Name Search Result**

Your Search was:

Last Name = WONG

First Name = LAWRENCE

Application#	Patent#	Status	Date Filed	Title	Inventor Name
09820079	7164206	150	03/28/2001	STRUCTURE IN A MICROELECTRONIC DEVICE INCLUDING A BI-LAYER FOR A DIFFUSION BARRIER AND AN ETCH-STOP LAYER	WONG, LAWRENCE
09968459	6992391	150	09/28/2001	DUAL-DAMASCENE INTERCONNECTS WITHOUT AN ETCH STOP LAYER BY ALTERNATING ILDS	WONG, LAWRENCE
10070012	6973297	150	07/29/2002	METHOD AND APPARATUS FOR DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS WITH REDUCED LOCAL OSCILLATOR LEAKAGE	WONG, LAWRENCE
10070280	7046980	150	07/29/2002	METHOD AND APPARATUS FOR UP-AND DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS	WONG, LAWRENCE
10328806	Not Issued	161	12/23/2002	Method of making semiconductor devices using carbon nitride, a low-dielectric-constant hard mask and/or etch stop	WONG, LAWRENCE
10363158	7215931	150	08/01/2003	METHOD AND APPARATUS FOR UP-AND-DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS	WONG, LAWRENCE
11109241	Not Issued	41	04/18/2005	Thin passivation layer on 3D devices	WONG, LAWRENCE
11131740	Not Issued	161	05/17/2005	Dual-damascene interconnects without an etch stop layer by alternating ILDs	WONG, LAWRENCE
11289993	Not Issued	30	11/30/2005	Delta code messaging	WONG, LAWRENCE

<u>11733764</u>	Not Issued	25	04/11/2007	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY APPORTIONING POWER AMONG PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733767</u>	Not Issued	25	04/11/2007	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY APPORTIONING GROUND RETURN PATH IMPEDANCES AMONG PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733770</u>	Not Issued	30	04/11/2007	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY CONTROLLING RF PHASE BETWEEN OPPOSING ELECTRODES	WONG, LAWRENCE
<u>11733858</u>	Not Issued	25	04/11/2007	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY CONTROLLING A VARIABLE FREQUENCY COUPLED TO A HARMONIC RESONATOR	WONG, LAWRENCE
<u>11733913</u>	Not Issued	25	04/11/2007	PLASMA REACTOR WITH ION DISTRIBUTION UNIFORMITY CONTROLLER EMPLOYING PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733984</u>	Not Issued	25	04/11/2007	METHOD OF PROCESSING A WORKPIECE IN A PLASMA REACTOR WITH VARIABLE HEIGHT GROUND RETURN PATH TO CONTROL PLASMA ION DENSITY UNIFORMITY	WONG, LAWRENCE
<u>11734040</u>	Not Issued	25	04/11/2007	PLASMA REACTOR WITH WIDE PROCESS WINDOW EMPLOYING PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11738505</u>	Not Issued	25	04/22/2007	PLASMA PROCESSING APPARATUS	WONG, LAWRENCE
<u>11738507</u>	Not Issued	25	04/22/2007	PLASMA PROCESSING METHOD	WONG, LAWRENCE
<u>11828568</u>	Not Issued	17	07/26/2007	PLASMA REACTOR WITH REDUCED ELECTRICAL SKEW USING ELECTRICAL BYPASS ELEMENTS	WONG, LAWRENCE
<u>11828713</u>	Not Issued	17	07/26/2007	PLASMA REACTOR WITH REDUCED ELECTRICAL SKEW USING A CONDUCTIVE	WONG, LAWRENCE

BAFFLE					
<u>60652407</u>	Not Issued	159	02/12/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation or other supports	WONG, LAWRENCE
<u>60652713</u>	Not Issued	159	02/14/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation on other supports	WONG, LAWRENCE
<u>60654203</u>	Not Issued	159	02/18/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation or other supports	WONG, LAWRENCE
<u>60898632</u>	Not Issued	20	01/30/2007	Multi-frequency capacitively coupled plasma source with uniformity control by spectral power apportionment	WONG, LAWRENCE
<u>09516650</u>	<u>6566757</u>	150	03/01/2000	STABILIZATION OF LOW DIELECTRIC CONSTANT FILM WITH IN SITU CAPPING LAYER	WONG, LAWRENCE D.
<u>09537160</u>	Not Issued	161	03/29/2000	Method for modifying the surface of a fluorocarbon	WONG, LAWRENCE D.
<u>09639625</u>	<u>6846737</u>	150	08/15/2000	PLASMA INDUCED DEPLETION OF FLUORINE FROM SURFACES OF FLUORINATED LOW-K DIELECTRIC MATERIALS	WONG, LAWRENCE D.
<u>09745397</u>	<u>6703324</u>	150	12/21/2000	MECHANICALLY REINFORCED HIGHLY POROUS LOW DIELECTRIC CONSTANT FILMS	WONG, LAWRENCE D.
<u>09745705</u>	<u>6984581</u>	150	12/21/2000	STRUCTURAL REINFORCEMENT OF HIGHLY POROUS LOW K DIELECTRIC FILMS BY ILD POSTS	WONG, LAWRENCE D.
<u>09747701</u>	<u>6432811</u>	150	12/20/2000	Method of forming structural reinforcement of highly porous low k dielectric films by Cu diffusion barrier structures	WONG, LAWRENCE D.
<u>09808758</u>	<u>6472315</u>	150	03/14/2001	METHOD OF VIA PATTERING UTILIZING HARD MASK AND STRIPPING PATTERNING MATERIAL AT LOW TEMPERATURE	WONG, LAWRENCE D.

<u>10025260</u>	Not Issued	161	12/17/2001	Structural reinforcement of highly porous low k dielectric films by ILD posts	WONG, LAWRENCE D.
<u>10050463</u>	<u>6593650</u>	150	01/15/2002	PLASMA INDUCED DEPLETION OF FLUORINE FROM SURFACES OF FLUORINATED LOW-K DIELECTRIC MATERIALS	WONG, LAWRENCE D.
<u>10153982</u>	<u>7115995</u>	150	05/22/2002	STRUCTURAL REINFORCEMENT OF HIGHLY POROUS LOW K DIELECTRIC FILMS BY CU DIFFUSION BARRIER STRUCTURES	WONG, LAWRENCE D.
<u>10161104</u>	<u>6734533</u>	150	05/30/2002	ELECTRON-BEAM TREATED CDO FILMS	WONG, LAWRENCE D.
<u>10654299</u>	Not Issued EB -	149	09/02/2003 no CDO	Mechanically reinforced highly porous low dielectric constant films	WONG, LAWRENCE D.
<u>10802331</u> <i>Hanne</i>	Not Issued	41	03/16/2004	Electron-beam treated CDO films	WONG, LAWRENCE D.
<u>10802991</u>	Not Issued	30	03/16/2004	Electron-beam treated CDO films	WONG, LAWRENCE D.
<u>11037860</u>	<u>7192856</u>	150	01/18/2005	FORMING DUAL METAL COMPLEMENTARY METAL OXIDE SEMICONDUCTOR INTEGRATED CIRCUITS	WONG, LAWRENCE D.
<u>08978106</u>	<u>6057226</u>	150	11/25/1997	AIR GAP BASED LOW DIELECTRIC CONSTANT INTERCONNECT STRUCTURE AND METHOD OF MAKING SAME	WONG, LAWRENCE D.
<u>09001509</u>	<u>6083839</u>	150	12/31/1997 ✓	UNIQUE CHEMICAL MECHANICAL PLANARIZATION APPROACH WHICH UTILIZES MAGNETIC SLURRY FOR POLISH AND MAGNETIC FIELDS FOR PROCESS CONTROL	WONG, LAWRENCE D.
<u>09001547</u>	<u>5946601</u>	150	12/31/1997 ✗	A UNIQUE a-C:N:H/a-C:NX FILM LINER/BARRIER TO PREVENT FLUORINE OUTDIFFUSION FROM a-FC CHEMICAL VAPOR DEPOSITION DIELECTRIC LAYERS	WONG, LAWRENCE D.

<u>09050707</u>	Not Issued	161	03/30/1998	A METHOD FOR FORMING AN INTERCONNECT SYSTEM USING A LOW DIELECTRIC CONSTANT LAYER	WONG, LAWRENCE D.
<u>09201580</u>	Not Issued	161	11/30/1998	STABILIZATION OF LOW DIELECTRIC CONSTANT FILM WITH IN SITU CAPPING LAYER	WONG, LAWRENCE D.
<u>09352634</u>	6284091	150	07/13/1999	UNIQUE CHEMICAL MECHANICAL PLANARIZATION APPROACH WHICH UTILIZES MAGNETIC SLURRY FOR POLISH AND MAGNETIC FIELDS FOR PROCESS CONTROL	WONG, LAWRENCE D.
<u>09458547</u>	6417098	150	12/09/1999	ENHANCED SURFACE MODIFICATION OF LOW K CARBON-DOPED OXIDE	WONG, LAWRENCE D.
<u>10097328</u> no BB	Not Issued no op's	41	03/15/2002	Method of making a semiconductor device using a damascene interconnect with a laminated dielectric	WONG, LAWRENCE D.
<u>10105431</u>	7214594	150	03/26/2002	METHOD OF MAKING SEMICONDUCTOR DEVICE USING A NOVEL INTERCONNECT CLADDING LAYER	WONG, LAWRENCE D.
<u>10194523</u>	7022478	150	07/11/2002	METHODS FOR EVALUATING STROKE OR CARDIAC ISCHEMIA BY NUCLEIC ACID DETECTION	WONG, LAWRENCE KA SING
<u>60380719</u>	Not Issued	159	05/14/2002	Methods for evaluating stroke or cardiac ischemia by nucleic acid detection	WONG, LAWRENCE KA SING

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